

PATENT
Atty. Dkt. No. AMAT/5908/CPI/ALUMINUM/PJS

IN THE CLAIMS:

Please cancel claims 1-54 without prejudice and amend the claims as follows:

1-54. (Canceled)

55. (Currently Amended) A semiconductor wafer processing system, comprising:

a first chamber and a second chamber respectively enclosing a first robot and a second robot, the first and second chambers each having one or more processing chambers attached thereto;

a load lock comprising a heating element and attached to the first chamber; and two or more transition chambers which separate the first and second chambers, the transition chambers each comprising a heating element disposed therein.

56. (Original) The semiconductor wafer processing system of claim 55, wherein the transition chamber heating element comprises a lamp.

57. (Original) The semiconductor wafer processing system of claim 56, wherein the transition chambers each comprise two wafer holders.

58. (Original) The semiconductor wafer processing system of claim 57, wherein the transition chambers each comprise a cooling plate.

59. (Original) The semiconductor wafer processing system of claim 55, wherein the transition chamber heating element comprises a resistive heater.

60. (Original) The semiconductor wafer processing system of claim 59, wherein the transition chambers each comprise a wafer holder.

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61. (Currently Amended) A semiconductor wafer processing system, comprising:

a chamber enclosing first and second robots and having one or more processing chambers attached thereto;

a load lock comprising a heating element, the load lock being attached to the chamber; and

two or more transition chambers within the chamber, each transition chamber comprising a heating element disposed therein.

62. (Original) The semiconductor wafer processing system of claim 61, wherein the transition chamber heating element comprises a lamp.

63. (Original) The semiconductor wafer processing system of claim 62, wherein the transition chambers each comprise two wafer holders.

64. (Original) The semiconductor wafer processing system of claim 63, wherein the transition chambers each comprise a cooling plate.